	Application No.	Applicant(s)	
Notice of Allowability	10/605,726	ZHU ET AL.	
	Examiner	Art Unit	
	Stephen W. Smoot	2813	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS nerewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31 1. This communication is responsive to applicant's amendments.	S (OR REMAINS) CLOSED in the community or other appropriate community of the community of t	nis application. If not included ication will be mailed in due c	d ourse. THIS
2. The allowed claim(s) is/are <u>1-19</u> .	•		
3. $igotimes$ The drawings filed on <u>06 May 2005</u> are accepted by the E	Examiner.		
 4. Acknowledgment is made of a claim for foreign priority upon a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17:2(a)). * Certified copies not received: 	re been received. re been received in Application	No	on from the
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONI THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a MENT of this application.	reply complying with the requ	iirements
5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give	nitted. Note the attached EXAN ves reason(s) why the oath or d	IINER'S AMENDMENT or NO eclaration is deficient.	TICE OF
6. CORRECTED DRAWINGS (as "replacement sheets") mu	ıst be submitted.		
(a) ☐ including changes required by the Notice of Draftsper	rson's Patent Drawing Review (PTO-948) attached	
1) hereto or 2) to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner Paper No./Mail Date	's Amendment / Comment or ir	the Office action of	
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on the the header according to 37 CFR	drawings in the front (not the late)	oack) of
 DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT 	osit of BIOLOGICAL MATER FOR THE DEPOSIT OF BIOL	RIAL must be submitted. No OGICAL MATERIAL.	ote the
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Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO-1449 or PTO/SB/Paper No./Mail Date 4. Examiner's Cornment Regarding Requirement for Deposit of Biological Material	6. Interview Sum Paper No./M /08), 7. Examiner's A	rmal Patent Application (PTOnmary (PTO-413), ail Date mendment/Comment tatement of Reasons for Allov	
Storler (W. Smoot	Stephen W. Smoot Patent Examiner Art Unit 2813	

Application/Control Number: 10/605,726

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This Office action is in response to applicant's amendment received on 06 May 2005.

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Graham S. Jones, II on 27 May 2005.

2. The application has been amended as follows:

In the Claims:

In claim 7, line 5, change "SiGe" to --silicon nitride--; and In claim 7, line 6, change "silicon nitride" to --SiGe--.

3. Replacement drawings were received on 06 May 2005. These drawings are acceptable.

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4. Claims 1-19 are allowed.

5. The following is an examiner's statement of reasons for allowance: Claims 1-19 are allowed because the prior art of record does not teach or suggest, in combination with the other claim limitations, a method of forming a device with a raised silicon source/drain and a gate electrode on an SOI structure that includes forming a SiGe layer over a silicon layer, forming a raised source/drain layer over the SiGe layer, etching a gate electrode opening through the raised source/drain layer and the SiGe layer to the surface of the silicon layer, lining the walls of the opening with inner spacers, forming the gate electrode between the inner spacers, and forming external spacers adjacent to the inner spacers.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Stephen W. Smoot whose telephone number is 571-272-1698. The examiner can normally be reached on M-F (8:00 am to 4:30 pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead, Jr. can be reached on 571-272-1702. The fax phone

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number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

SWS